

12/02/2008

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant:** Kwang Su Choe, et al.

**Examiner:** Marianne L. Padgett

**Serial No.:** 10/674,647

**Art Unit:** 1762

**Filed:** September 30, 2003

**Docket:** YOR920030293US1 (16818)

**For:** THIN BURIED OXIDES BY LOW-DOSE  
OXYGEN IMPLANTATION INTO MODIFIED  
SILICON

**Dated:** November 24, 2008

**Confirmation No:** 4796

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE UNDER 37 C.F.R. § 1.116**

Sir:

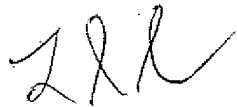
In response to the Office Action dated October 1, 2008, please consider the following amendments and remarks with respect to the above referenced application.

---

**CERTIFICATE OF ELECTRONIC FILING**

I hereby certify that this correspondence is being electronically filed with the United States Patent and Trademark Office e-business website on the date listed below.

Dated: November 24, 2008

  
\_\_\_\_\_  
Leslie S. Szivos